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Front Matter: Volume 6993

, "Front Matter: Volume 6993," Proc. SPIE 6993, MEMS, MOEMS, and Micromachining III, 699301 (12 May 2008); doi: 10.1117/12.797940

SPIE.

Event: SPIE Photonics Europe, 2008, Strasbourg, France

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MEMS, MOEMS, and Micromachining III

Hakan Urey

Editor

9–10 April 2008

Strasbourg, France

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Volume 6993

Proceedings of SPIE, 0277-786X, v. 6993

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Please use the following format to cite material from this book:

Author(s), "Title of Paper," in *MEMS, MOEMS, and Micromachining III*, edited by Hakan Urey, Proceedings of SPIE Vol. 6993 (SPIE, Bellingham, WA, 2008) Article CID Number.

ISSN 0277-786X

ISBN 9780819471918

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA

Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

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